



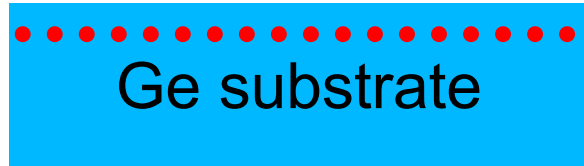
Research Consortium in Speckled Computing

Towards III-V's on GoI

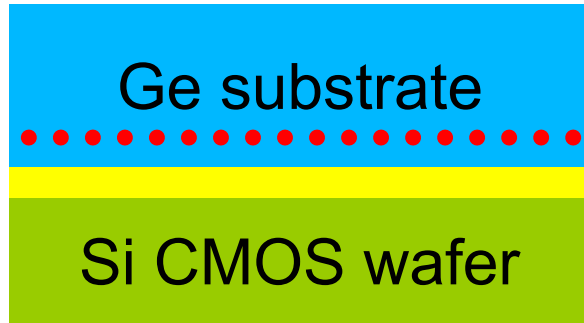
Subho Chakrabarti
University of Glasgow
C.Stanley@elec.gla.ac.uk
Supervisor: Colin Stanley



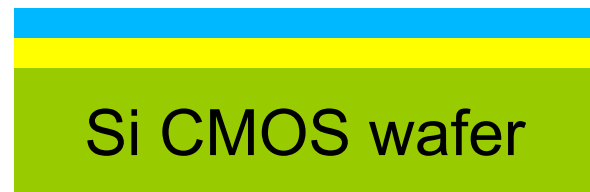
- Integration of functional electronic devices/ICs and photovoltaic power generators on a common platform.
- The common platform envisaged is Germanium-on-Insulator, or GoI for short.
 - Si wafer with CMOS processing circuitry embedded within it
 - Thin SiO₂ insulation layer over CMOS
 - Few microns thick, single crystal Ge template bonded to insulator-over-Si
 - Epitaxy of III-Vs on Ge



1. Implant hydrogen/helium ions to create plane of damage a few microns below the Ge wafer surface



2. Fuse Ge to Si (CMOS) wafer, with an intervening layer of SiO₂

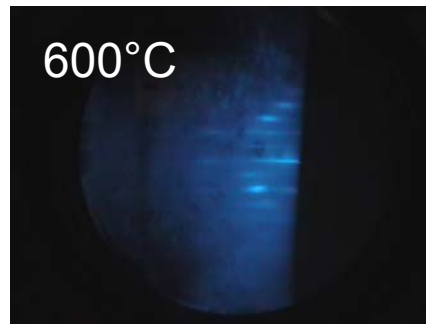
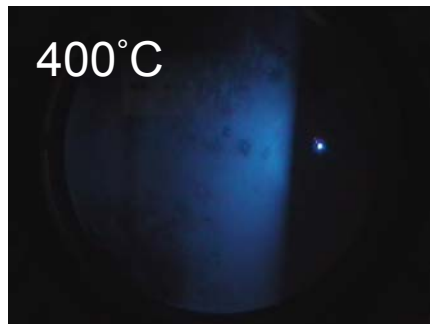


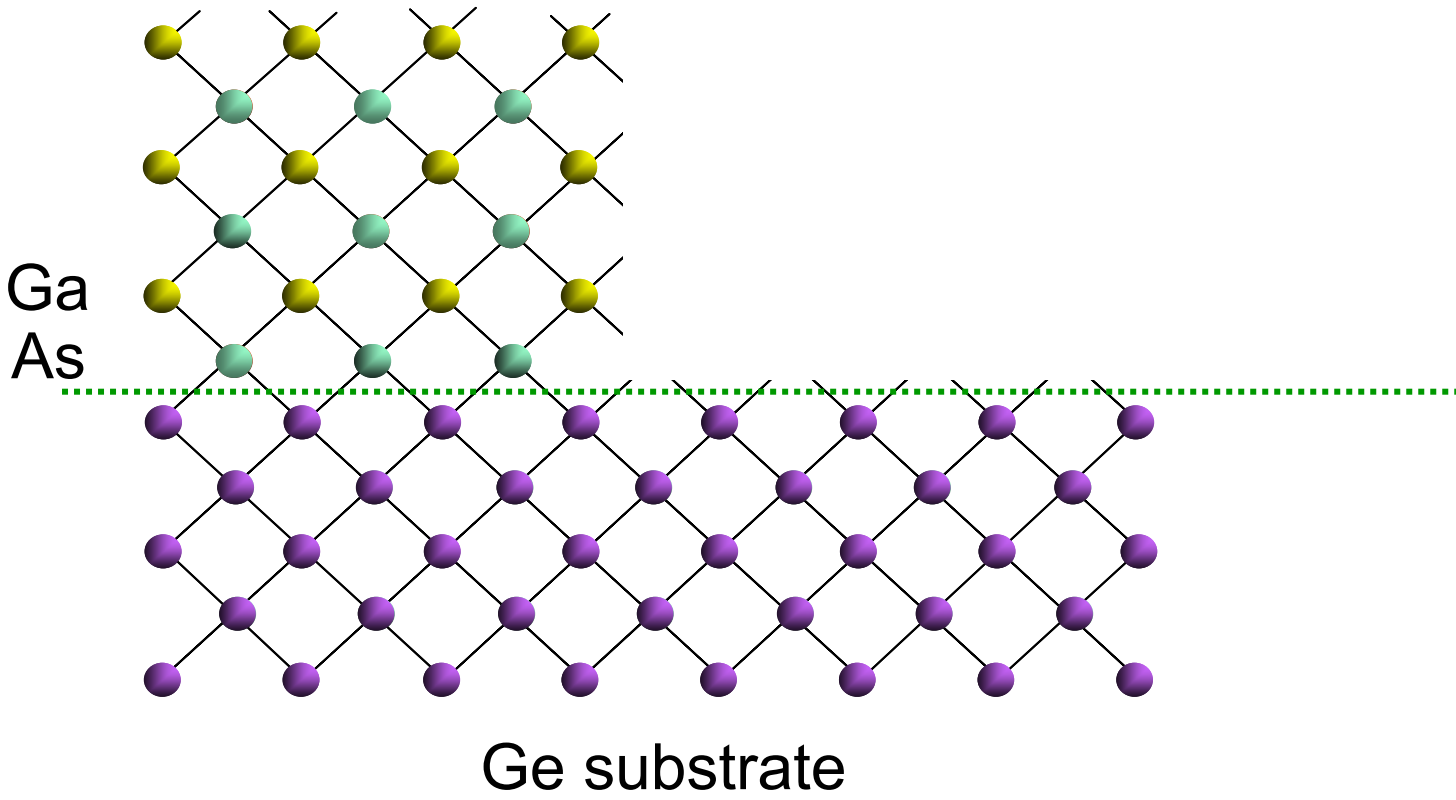
Ge template for epitaxy

3. Separate, polish, anneal to leave a thin Ge template bonded to Si (remainder of Ge wafer re-used)

- Small mismatch in lattice constants of Ge and (Al,Ga)As.
- Out-diffusion of Ge into GaAs.
- In-diffusion of As into Ge.
- Ge is a non-polar semiconductor, whereas GaAs is polar.
 - High risk of anti-phase domains since either Ga or As can bond to Ge
- Ge substrates with a 6° off-cut of (001) orientation toward the in-plane [100] direction are widely used.
- Initial MBE growth studies at Glasgow have been on Ge substrates rather than Ga

- Substrate degassed and Ge oxide(s) removed by a 20 min anneal at 640°C.
- Ideally, this should be followed by the deposition of an epitaxial Ge buffer layer prior to GaAs nucleation.
 - Ge source in MBE system produces a very low flux
 - Ge growth rate probably below 0.1 $\mu\text{m/hr}$
 - Improvements to wafer surface as monitored by *in situ* RHEED have been inconclusive





- Anti-phase domains (APDs) can be avoided by
 - **Migration Enhanced Epitaxy** of 10 monolayers (ML) GaAs at $\sim 350^\circ\text{C}$ and a growth rate of ~ 0.1 ML/s.
 - $\sim 0.1\mu\text{m}$ of **GaAs** at $\sim 500^\circ\text{C}$ and a growth rate of $\sim 0.1\mu\text{m/hr}$
 - $\sim 0.5\mu\text{m}$ of **GaAs** at $\sim 580^\circ\text{C}$ and a growth rate of $\sim 1.0\mu\text{m/hr}$
- An AlAs-GaAs superlattice may be required to provide electrical isolation of III-V device structure(s) from Ge.

Optional AlAs-GaAs SL

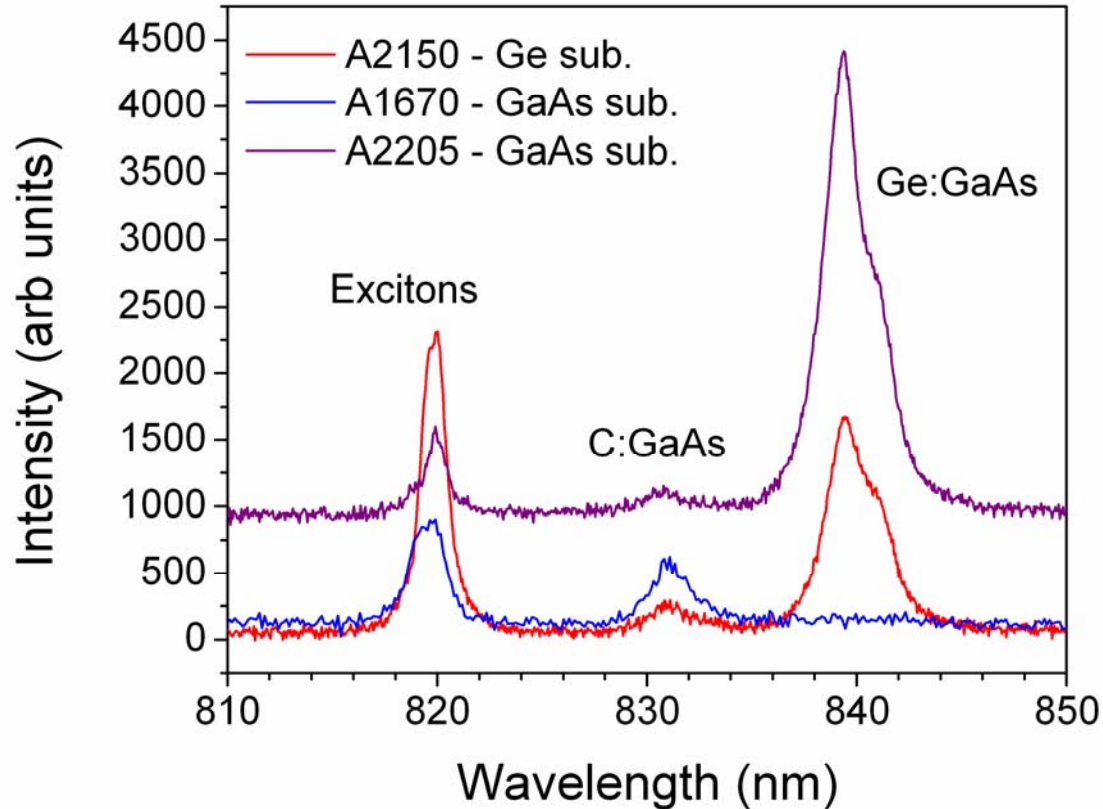
“Standard” GaAs buffer layer

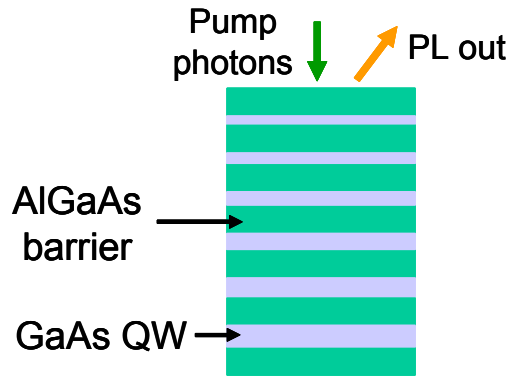
LT GaAs @ slow growth rate

Low temp. GaAs by MEE

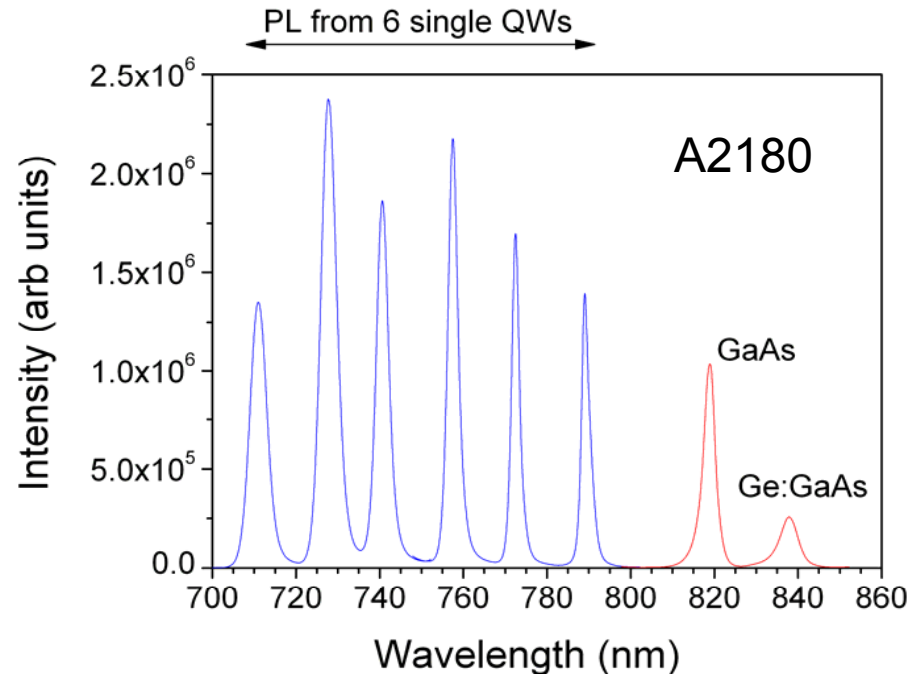
Ge substrate



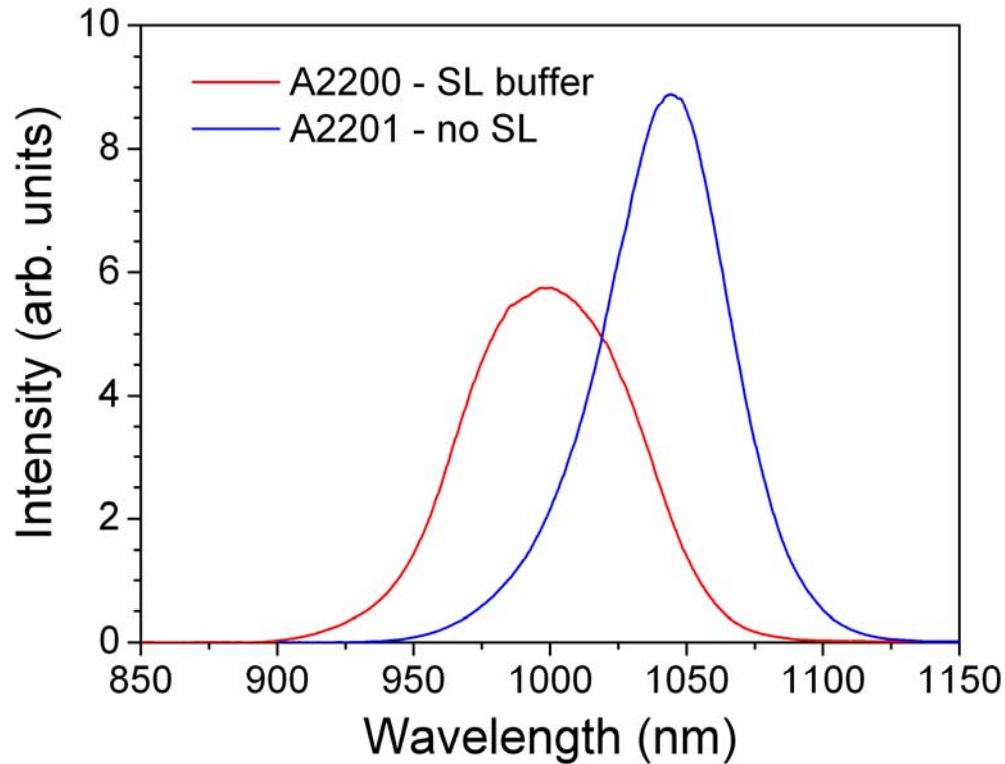




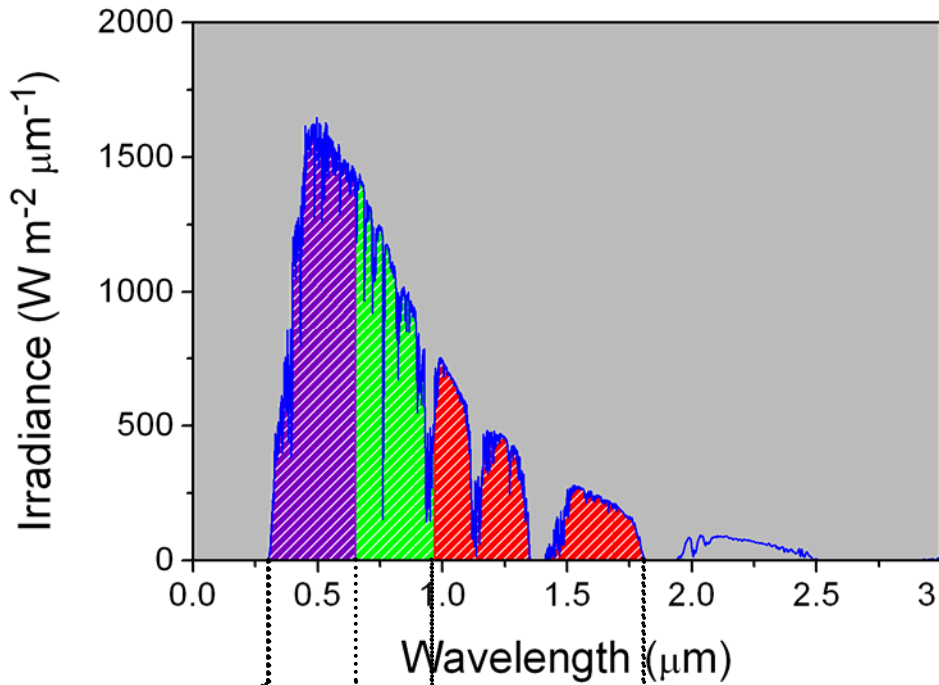
- SQWs grown on Ge (no Ge buffer)
 - 10ML of GaAs by MEE at 375°C)
 - 0.1 μm GaAs buffer @ 0.1 $\mu\text{m}/\text{hr}$ at 500°C
 - Repeated annealing at 580°C
 - 5 μm GaAs @ 1 $\mu\text{m}/\text{hr}$ at 580°C
- SQWs on Ge buffer layer gave no measureable PL emission.



- “Standard” AlGaAs-GaAs HEMT for reference.
 - Bench-marks unintentional impurity concentration in GaAs and roughness of 2-DEG interface
- 53% InGaAs channel metamorphic HEMT.
 - Includes buffer layer with graded In-composition and InGaAs-InAlAs superlattice
- Standard GaAs-AlGaAs solar cell.
- InGaAs quantum dot stacks (1100-1300nm laser-type structure).



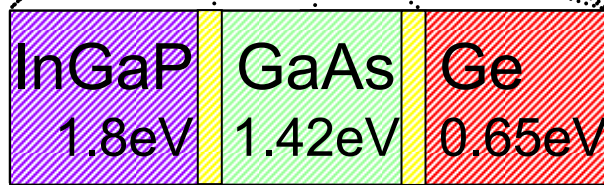
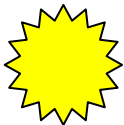
4 uncoupled layers of $\text{In}_{0.45}\text{Ga}_{0.55}\text{As}$ quantum dots



- Increase utilization of solar spectrum/reduce energy lost from thermalization of free carriers
 - Use a range of semiconductors to absorb segments of spectrum.
- PV cells connected in series
 - higher V_{oc} than single junction
 - reduced short circuit current, I_{sc} .

Major difficulties;

- tunnel junctions to interconnect cells.
- careful design to ensure each cell generates the same current.
- **sensitive to irradiance**

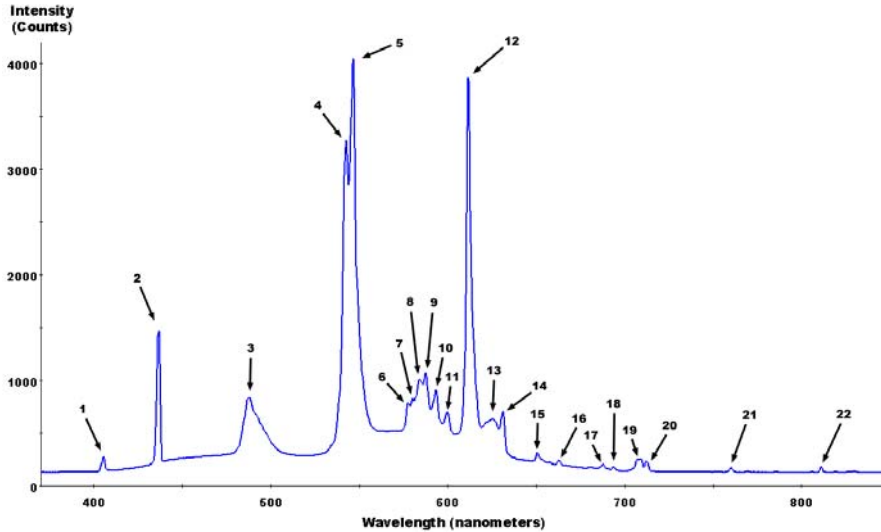


Tunnel junctions

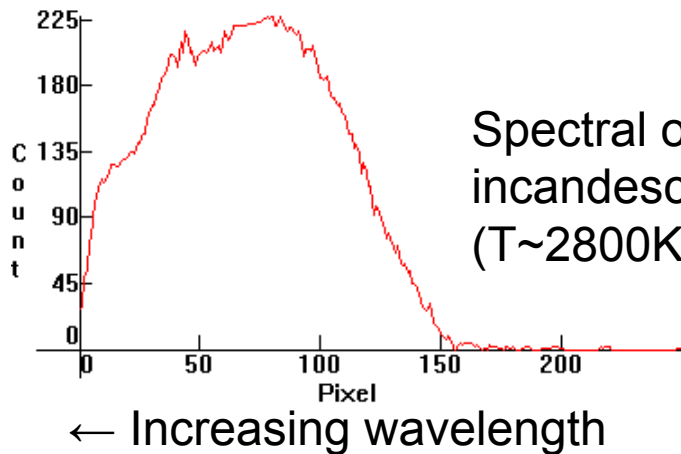
Speck

Spectral output of artificial light sources

Research Consortium in Speckled Computing



A typical "cool white" fluorescent lamp utilizing two rare earth doped phosphors, Tb^{3+} , $Ce^{3+}:LaPO_4$ for green and blue emission and $Eu:Y_2O_3$ for red. Several of the spectral peaks are directly generated from the mercury discharge.

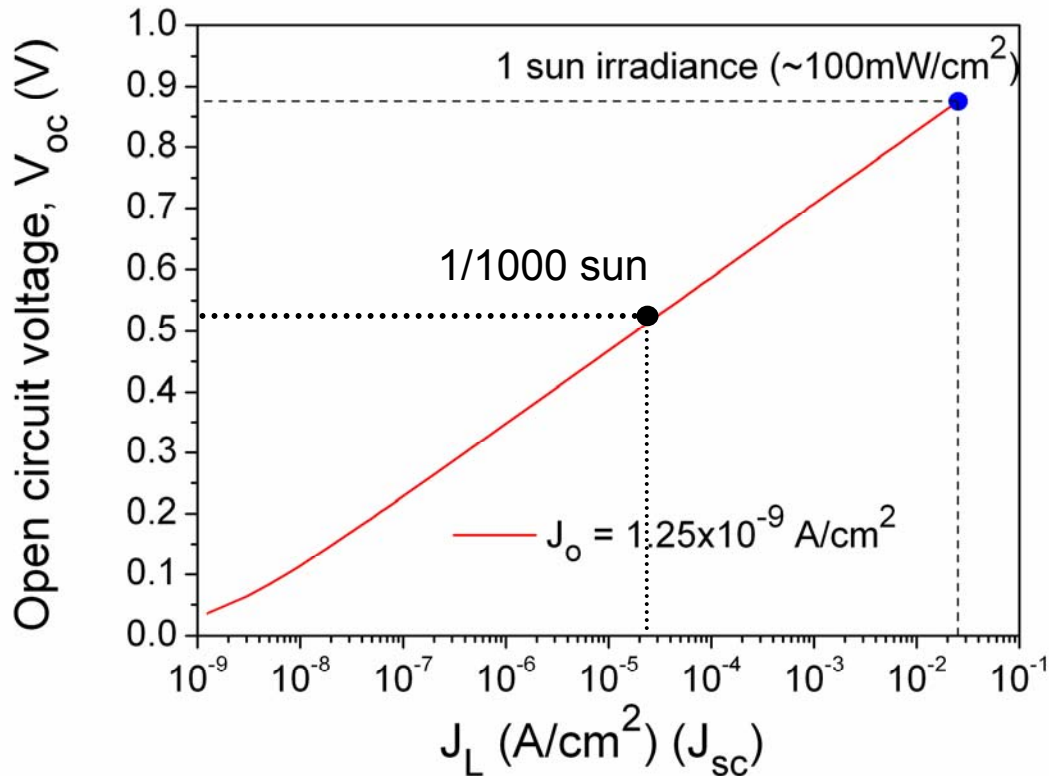


Spectral output of an incandescent light bulb ($T \sim 2800K$).

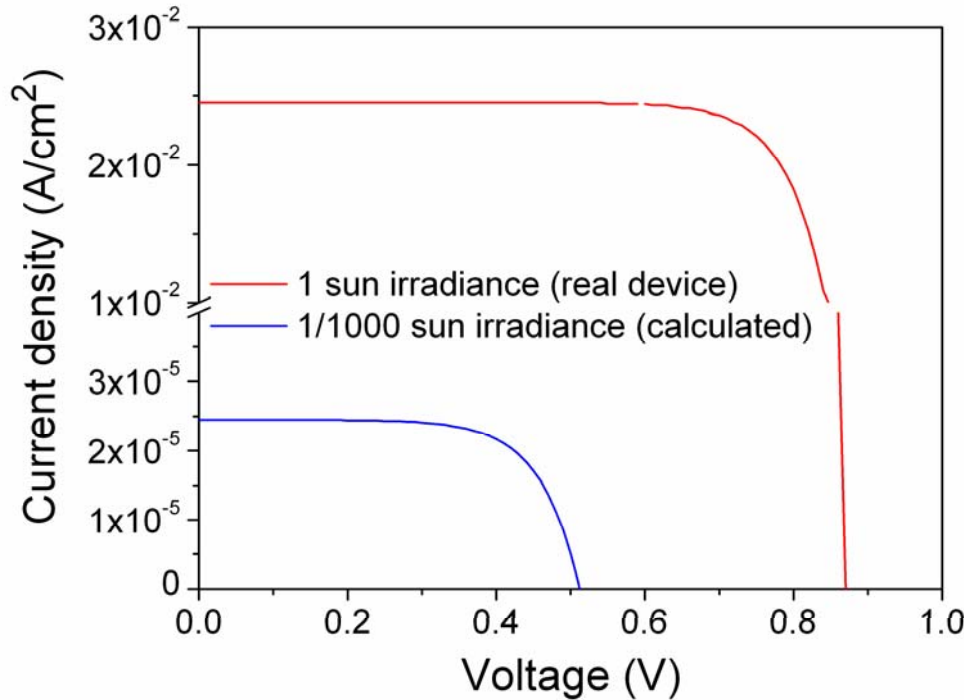
Output truncated above $\sim 1000nm$ due to response of Si detector



- Spectrum of artificial illumination important.
- Cells needs to be designed around the source for maximum power out.
- Single (Al)GaAs p-n junction might be the simplest implementation
 - Practical conversion efficiency ~25%, compared with ~40% for triple-junction terrestrial cells under **concentrated sunlight**
 - Max. open circuit voltage, V_{oc} of ~1.0 V, but this depends on the current created by illumination (I_L)
 - Short circuit current (max I), $I_{sc} = -I_L$



$$V_{oc} = \frac{nk_B T}{q} \ln \left[\frac{I_L}{I_o} + 1 \right]$$



- These curves are based on 1 sun irradiance.
- I_{sc} scales with linearly irradiance.
- The output under illumination with artificial light will depend on the spectral content of the source.

Under 1/1000 sun illumination, the voltage at maximum output power is ~0.4V, with a current ~20 μ A/cm²

- Connect cells in series to achieve output voltage.
 - Wider band-gap PV cell for fluorescent lights? Higher V_{oc}
- Connect strings of series-connected cells in parallel, to achieve desired output current.
- $V \sim 4-4.2$ volts with $I \sim 10-20 \mu A$ can potentially be generated by an 10×10 array of single junction GaAs PV cells covering an area of $\sim 1 \text{cm}^2$.

